



ifu

PATENT

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of	)	
Bright et al.	)	Examiner: G.B.M. Nguyen
Application No. 10/722,839	)	Group Art Unit: 3723
Filed: November 25, 2003	)	Docket No: LAM2P318D
For: APPARATUS FOR CONTROLLING	)	Date: March 21, 2005
WAFER TEMPERATURE IN CHEMICAL	)	
MECHANICAL POLISHING	)	

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on March 21, 2005.

Signed: \_\_\_\_\_

Ray Harlow

REQUEST FOR CORRECTED FILING RECEIPT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

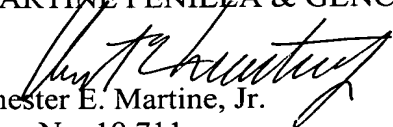
Sir:

Enclosed is a copy of the Filing Receipt for the above-identified patent application. Please reprint the Filing Receipt as follows and mail the corrected copy to the undersigned.

Please change the title from "Apparatus methods for controlling wafer temperature in chemical mechanical polishing " to – Apparatus for controlling wafer temperature in chemical mechanical polishing --.

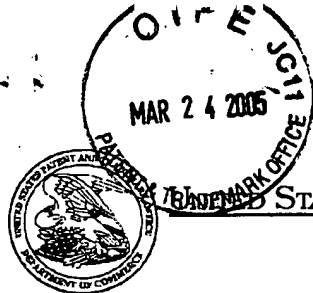
The Commissioner is authorized to charge any fees that may be due to Deposit Account 50-0805 (Order No. LAM2P318D).

Respectfully submitted,  
MARTINE PENILLA & GENCARELLA, LLP

  
Chester E. Martine, Jr.  
Reg. No. 19,711

Telephone (408) 774-6908  
Facsimile: (408) 749-6901  
Customer Number 25920

Attorney Docket No. LAM2P318D



## UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE  
 United States Patent and Trademark Office  
 Address: COMMISSIONER FOR PATENTS  
 P.O. Box 1450  
 Alexandria, Virginia 22313-1450  
 www.uspto.gov

APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/722,839	11/25/2003	3723	770	LAM2P318D	9	15	3

CONFIRMATION NO. 8198

25920  
 MARTINE & PENILLA, LLP  
 710 LAKEWAY DRIVE  
 SUITE 170  
 SUNNYVALE, CA 94085

## FILING RECEIPT



\*OC000000012012119\*

Date Mailed: 03/03/2004

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Filing Receipt Corrections, facsimile number 703-746-9195. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

## Applicant(s)

Nicolas Bright, San Jose, CA;  
 David J. Hemker, San Jose, CA;

## Assignment For Published Patent Application

LAM Research Corporation;

## Domestic Priority data as claimed by applicant

This application is a DIV of 10/033,455 12/26/2001

## Foreign Applications

If Required, Foreign Filing License Granted: 03/01/2004

Projected Publication Date: 06/10/2004

Non-Publication Request: No

Early Publication Request: No

## Title

Apparatus-methods for controlling wafer temperature in chemical mechanical polishing

**Preliminary Class**

438

---

**LICENSE FOR FOREIGN FILING UNDER  
Title 35, United States Code, Section 184  
Title 37, Code of Federal Regulations, 5.11 & 5.15**

**GRANTED**

The applicant has been granted a license under 35 U.S.C. 184, if the phrase "IF REQUIRED, FOREIGN FILING LICENSE GRANTED" followed by a date appears on this form. Such licenses are issued in all applications where the conditions for issuance of a license have been met, regardless of whether or not a license may be required as set forth in 37 CFR 5.15. The scope and limitations of this license are set forth in 37 CFR 5.15(a) unless an earlier license has been issued under 37 CFR 5.15(b). The license is subject to revocation upon written notification. The date indicated is the effective date of the license, unless an earlier license of similar scope has been granted under 37 CFR 5.13 or 5.14.

This license is to be retained by the licensee and may be used at any time on or after the effective date thereof unless it is revoked. This license is automatically transferred to any related applications(s) filed under 37 CFR 1.53(d). This license is not retroactive.

The grant of a license does not in any way lessen the responsibility of a licensee for the security of the subject matter as imposed by any Government contract or the provisions of existing laws relating to espionage and the national security or the export of technical data. Licensees should apprise themselves of current regulations especially with respect to certain countries, of other agencies, particularly the Office of Defense Trade Controls, Department of State (with respect to Arms, Munitions and Implements of War (22 CFR 121-128)); the Office of Export Administration, Department of Commerce (15 CFR 370.10 (j)); the Office of Foreign Assets Control, Department of Treasury (31 CFR Parts 500+) and the Department of Energy.

**NOT GRANTED**

No license under 35 U.S.C. 184 has been granted at this time, if the phrase "IF REQUIRED, FOREIGN FILING LICENSE GRANTED" DOES NOT appear on this form. Applicant may still petition for a license under 37 CFR 5.12, if a license is desired before the expiration of 6 months from the filing date of the application. If 6 months has lapsed from the filing date of this application and the licensee has not received any indication of a secrecy order under 35 U.S.C. 181, the licensee may foreign file the application pursuant to 37 CFR 5.15(b).